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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

IN RE APPLICATION OF YOUNG HOON PARK

FOR: ATOMIC LAYER DEPOSITION (ALD) THIN FILM DEPOSITION
EQUIPMENT HAVING CLEANING APPARATUS AND CLEANING
METHOD

PRELIMINARY AMENDMENT

The Assistant Commissioner of
Patents and Trademarks
Washington, DC 20231

Dear Sir:

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Jennifer Matson
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Jennifer Matson
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Before examining the present application, please amend as follows:

IN THE SPECIFICATION:

Please accept the following specification paragraphs in re-written "clean form". The following paragraphs are the second to fifth paragraphs in the section entitled "SUMMARY OF THE INVENTION".

To achieve the above objective, the present invention provides an atomic layer deposition (ALD) thin film deposition equipment having a cleaning apparatus, this equipment including: a reactor in which a wafer is mounted and a thin film is deposited on the wafer; a first reaction gas supply portion for supplying a first reaction gas to the reactor; a second reaction gas supply portion for supplying a second reaction gas to the reactor; a first reaction gas supply line for connecting the first reaction gas supply portion to the reactor; a second reaction gas supply line for connecting the second reaction gas supply portion to the reactor; a first inert gas supply line for supplying an inert gas from